**Description**

Two high temperature compact reactors CTR 125 provide both atmospheric pressure (CVD) and Low vacuum (LPCVD) chemical vapor deposition processes.

The CVD system is used for silicon oxide (SiO$_2$) films on silicon wafer by means of its diffusion.

The LPCVD system is used for deposit of amorphous- or poly- silicon on substrates.

**Specifications / Capabilities**

Production style performance in a small footprint;
Fully automated, recipe driven processing.
LPCVD & CVD up to 4” wafer size and 25 wafers in one cycle

**Applications**

Thermal Oxide or Silicon Dioxide (SiO$_2$) is the insulating layer commonly used in semiconductors.

Amorphous silicon (a-Si) is the non-crystalline form of Si used for solar cells and thin film transistors in LCD displays.

Solar cells, MEMS etc...

**Materials**

**Link**

http://www.exper-tech.com/
http://www.exper-tech.com/products/compact-thermal-reactor/